

AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

1. (Currently Amended) A porous-material-forming photo-curing resin composition, comprising:

a photo-polymerizable monomer (A) comprising a fluorine atom or a silicon atom and having a surface tension of not more than 25×10^{-5} N/cm,

water or an organic compound (B) having a surface tension of not less than 40×10^{-5} N/cm, that is the water or the organic compound (B) being non-compatible with the photo-polymerizable monomer (A),

a common solvent (C) that is an organic solvent having a surface tension in a range of 25×10^{-5} to 35×10^{-5} N/cm and is compatible with the photo-polymerizable monomer (A) and the water or the organic compound (B); and

a photo-polymerization initiator (D).

2. (Cancelled)

3. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 1 [[or 2]], further comprising other photo-polymerizable monomers other than the photo-polymerizable monomer (A), [[and]]

wherein a blending amount of the other photo-polymerizable monomers is not more than 90% by weight of the entire amount of the photo-polymerizable monomers.

4. (Cancelled)

5. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 1 [[or 2]], wherein water is used together with an organic compound (B) as [[the]] component that is non-compatible with the photo-polymerizable monomer (A) ~~is water~~.

6. (Cancelled)

7. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 1 [[or 2]], wherein the photo-polymerizable monomer (A) comprises a (metha)acryloyl group or a vinyl group as a photo-polymerizable group.

8. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 1 [[or 2]], wherein the organic compound (B) comprises one or more kinds of groups ~~and/or~~ or bonds selected from the group consisting of a hydroxide group, an amino group, a ketone bond, a sulfide bond, a sulfoxide bond and a cyclic amide bond.

9. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 1 [[or 2]], wherein the common solvent (C) is an aromatic or alicyclic hydrocarbon solvent, an oxygen-containing solvent or a nitrogen-containing solvent.

10. (Currently Amended) A porous resin cured product which is obtained by photo-curing the porous-material-forming photo-curing resin composition according to claim 1 [[or 2]].

11. (Currently Amended) The porous resin cured product ~~according to claim 10~~, which is obtained by removing the organic compound (B) or water and the common solvent (C) contained ~~therein~~ in the porous resin cured product according to claim 10.

12. (Previously Presented) The porous resin cured product according to claim 10, which has a film shape or a sheet shape.

13. (Previously Presented) The porous resin cured product according to claim 10, which has a substrate on at least one face.

14. (Currently Amended) A liquid crystal display element comprising the porous resin cured product according to claim ~~[[10]]~~ 11 as a supporting material.

15. (Currently Amended) A liquid crystal recording material comprising the porous resin cured product according to claim ~~[[10]]~~ 11 as a supporting material.

16. (Cancelled)

17. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 3, wherein water is used together with the organic compound (B) as [[the]] component that is non-compatible with the photo-polymerizable monomer (A) ~~is water~~.

18. (Cancelled)

19. (Previously Presented) The porous-material-forming photo-curing resin composition according to claim 3, wherein the photo-polymerizable monomer (A) comprises a (metha)acryloyl group or a vinyl group as a photo-polymerizable group.

20. (Currently Amended) The porous-material-forming photo-curing resin composition according to claim 3, wherein the organic compound (B) comprises one or more kinds of groups ~~and/or~~ or bonds selected from the group consisting of a hydroxide group, an amino group, a ketone bond, a sulfide bond, a sulfoxide bond and a cyclic amide bond.

21. (Previously Presented) The porous-material-forming photo-curing resin composition according to claim 3, wherein the common solvent (C) is an aromatic or alicyclic hydrocarbon solvent, an oxygen-containing solvent or a nitrogen-containing solvent.

22. (Previously Presented) A porous resin cured product which is obtained by photo-curing the porous-material-forming photo-curing resin composition according to claim 3.

23. (Cancelled)

24. (New) The porous-material-forming photo-curing resin composition according to claim 5, wherein the photo-polymerizable monomer (A) comprises a (metha)acryloyl group or a vinyl group as a photo-polymerizable group.

25. (New) The porous-material-forming photo-curing resin composition according to claim 5, wherein the organic compound (B) comprises one or more kinds of groups or bonds selected from the group consisting of a hydroxide group, an amino group, a ketone bond, a sulfide bond, a sulfoxide bond and a cyclic amide bond.

26. (New) The porous-material-forming photo-curing resin composition according to claim 5, wherein the common solvent (C) is an aromatic or alicyclic hydrocarbon solvent, an oxygen-containing solvent or a nitrogen-containing solvent.

27. (New) A porous resin cured product which is obtained by photo-curing the porous-material-forming photo-curing resin composition according to claim 5.

28. (New) The porous resin cured product, which is obtained by removing the organic compound (B) or water and the common solvent (C) contained in the porous resin cured product according to claim 27.

29. (New) The porous resin cured product according to claim 27, which has a film shape or a sheet shape.

30. (New) The porous resin cured product according to claim 27, which has a substrate on at least one face.

31. (New) A liquid crystal display element comprising the porous resin cured product according to claim 28 as a supporting material.

32. (New) A liquid crystal recording material comprising the porous resin cured product according to claim 28 as a supporting material.

33. (New) The porous-material-forming photo-curing resin composition according to claim 17, wherein the photo-polymerizable monomer (A) comprises a (metha)acryloyl group or a vinyl group as a photo-polymerizable group.

34. (New) The porous-material-forming photo-curing resin composition according to claim 17, wherein the organic compound (B) comprises one or more kinds of groups or bonds selected from the group consisting of a hydroxide group, an amino group, a ketone bond, a sulfide bond, a sulfoxide bond and a cyclic amide bond.

35. (New) The porous-material-forming photo-curing resin composition according to claim 17, wherein the common solvent (C) is an aromatic or alicyclic hydrocarbon solvent, an oxygen-containing solvent or a nitrogen-containing solvent.

36. (New) A porous resin cured product which is obtained by photo-curing the porous-material-forming photo-curing resin composition according to claim 17.